

Crystallographic and Magnetic Properties of CoCrPt Thin Films Investigated Using Single-Crystal Perpendicular Magnetic Thin Film Samples

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ABSTRACT

Conditions to prepare good single-crystal CoCrPt magnetic thin film with the easy magnetization axis perpendicular to the film plane were investigated using oxide single-crystal substrates, Al₂O₃(0001), LaAlO₃(0001), mica(0001), SrTiO₃(111), and MgO(111). The best CoCrPt(0001) single-crystal thin film was obtained on an Al₂O₃(0001) substrate employing a non-magnetic CoCrRu underlayer. The crystallographic quality of single-crystal thin film was investigated using X-ray diffraction and high-resolution transmission electron microscopy. Some intrinsic magnetic properties (H_k, K_u) were determined for the single-crystal CoCr_xPt_y thin films for a compositional range of $x=17 - 20\text{at}\%$ and $y=0 - 17\text{at}\%$.

INTRODUCTION

Co-based alloy thin films are used as magnetic recording media in hard disk drives. The areal density will continuously increase to 100 – 200 Gb/in² in the near future. Perpendicular magnetic recording is expected to replace longitudinal magnetic recording to keep the thermal stability of recorded information at high densities. Improvements of magnetic properties while enhancing thermal stability are important issues for designing perpendicular magnetic recording media. The thermal stability and recording characteristics of future recording media have been studied mainly by computer simulation employing basic magnetic properties of Co-alloy materials such as magneto-crystalline anisotropy energy (K_u), exchange stiffness constant, Curie temperature, etc. However it has not been easy to determine these intrinsic basic magnetic properties using a polycrystalline magnetic thin film which consists of very small crystalline grains with complicated microstructure. In order to investigate the basic magnetic properties accurately, it is desirable to use well-defined single-crystal thin films.

Single crystalline Co-based alloy thin films with the easy magnetization axis perpendicular to the film plane have been prepared using Ti and Ru underlayers on mica(0001) substrates [1,2], and using a Ti/Ag composite underlayer on Si(111) substrates [3]. However, the Co-based alloy single-crystalline thin films are reported to include some crystallographic defects such as sub-grain boundaries and a small fraction of *fcc* Co-alloy. We have recently found that Co-alloy single-crystal thin films with the *c*-axis

perpendicular to the film plane can be grown on oxide single-crystal substrates [4] and that the crystallographic quality depends strongly on the substrate and underlayer materials.

In the present work, effects of substrate and underlayer materials on the crystallographic quality of CoCrPt alloy magnetic thin films will be discussed based on the structural analysis using X-ray diffraction and transmission electron microscopy studies. Using the optimized condition in growing good single-crystal thin films, CoCrPt alloy thin films with different compositions are prepared to investigate the basic magnetic properties.

EXPERIMENTAL PROCEDURE

Single-crystal oxides of $\text{Al}_2\text{O}_3(0001)$, $\text{LaAlO}_3(0001)$, mica(0001), $\text{SrTiO}_3(111)$, and $\text{MgO}(111)$ were chosen as possible substrates to grow exitaxial CoCrPt magnetic thin films with the *hcp*-basal plane (0001) parallel to the substrate surface. These oxide single-crystals were selected by taking into account the arrangements of metallic atoms in the surface which may affect the epitaxial growth of metallic films with *hcp* structure. The lattice misfit of CoCrPt layer against substrate material was ranged from nearly zero (mica) to more than 10 % (MgO). A DC magnetron sputtering system with the base pressure below 1×10^{-10} Torr was used to prepare thin film samples [5]. The background pressure increased to about 1×10^{-9} Torr when the substrates were heated to 500 – 600 K using lamp heaters. Non-magnetic underlayer materials with *hcp* crystal structure, TiCr_{10} , CoCr_{40} , $\text{CoCr}_{25}\text{Ru}_{25}$, $\text{CoCr}_{25}\text{Ru}_{25}/\text{Ti}$, were employed. A non-magnetic underlayer and a $\text{CoCr}_{19}\text{Pt}_{10}$ magnetic layer were sequentially sputter-deposited on oxide single-crystal substrates kept at 533 K. Before sputter deposition, the substrates were kept on a heating stage in the deposition chamber for about an hour to remove the surface contamination and to saturate the substrate temperature. The deposition rates were 1.7 – 1.8 nm/s for the Co-alloy materials and 0.8 – 0.9 nm/s for the Ti and TiCr materials, respectively. The composition of CoCr_xPt_y magnetic layer was also varied by changing the sputtering target composition in the range for $y=0-17$ at% while trying to keep the Cr content to be constant at around $x=18$ at%. The CoCr_xPt_y magnetic layer thickness was varied between 6 and 100 nm.

The sample structure was investigated by X-ray diffraction employing θ - 2θ , rocking curve and pole-figure techniques. Cross-sectional and plan-view sample structures were observed by using a high-resolution transmission electron microscope (TEM). Microscopic compositional distributions of alloy elements were studied by TEM equipped with a chemical analysis facility. A focused electron beam of 2 nm in diameter was employed in the electron-probe micro analysis (EPMA) to determine the local compositional variations.

RESULTS AND DISCUSSION

Effect of substrate material

Table I summarizes the experimental results. Here a $\text{CoCr}_{25}\text{Ru}_{25}$ (50 nm) non-magnetic underlayer and a $\text{CoCr}_{19}\text{Pt}_{10}$ (25 nm) magnetic layer were sequentially deposited on various substrates in the sputter deposition system simultaneously. Single-crystal thin films were obtained on Al_2O_3 (0001), LaAlO_3 (0001), and SrTiO_3 (111) substrates, while polycrystalline thin films grew on mica(0001), MgO (111), and glass substrates. The glass substrate was used as a reference. The result that a

Table I Lattice parameters of substrate materials and results of X-ray analysis on $\text{CoCrPt}/\text{CoCrRu}$ bi-layers formed on various single-crystal oxides.

Material	Al_2O_3 (0001)	LaAlO_3 (0001)	Mica (0001)	SrTiO_3 (111)	MgO (111)	Glass (reference)
Crystal structure	hexagonal	hexagonal	hexagonal	cubic	cubic	(amorphous)
Lattice constant						
a (nm)	0.475	0.537	0.518	$\sqrt{2}a=0.552$	$\sqrt{2}a=0.595$	-
c (nm)	1.299	1.311	20.99	-	-	-
Mismatch ¹⁾ (%)	-6.1 ²⁾	-3.9 ³⁾	-0.4 ³⁾	-6.5 ⁴⁾	-13.3 ⁴⁾	-
Results of X-ray analysis						
I_{0002} (cps)	99200	13200	7400	8300	4600	1900
$\Delta\theta_{50}$ (degs)	0.6	2.6	5.3	5.1	6.3	7.6
Film quality	single-crystal	single-crystal	poly-crystal	single-crystal	poly-crystal	poly-crystal

Sample structure: $\text{CoCrPt}(25\text{nm})/\text{CoCrRu}(50\text{nm})/\text{Oxide}$ single-crystal substrate.

1) Mismatch is calculated for the lattice parameter of $\text{CoCr}_{25}\text{Ru}_{25}$ non-magnetic underlayer, $2a=2 \times 0.258$ nm.

2) $\text{Al}_2\text{O}_3(0001)/\text{CoCr-alloy}(0001)$, $\text{Al}_2\text{O}_3[10.0]/\text{CoCr-alloy}[21.0]$

3) $\text{LaAlO}_3(0001)$ and mica(0001)// $\text{CoCr-alloy}(0001)$, $\text{LaAlO}_3[10.0]$ and mica[10.0]// $\text{CoCr-alloy}[10.0]$.

4) $\text{SrTiO}_3(111)$ and $\text{MgO}(111)/\text{CoCr-alloy}(0001)$, $\text{SrTiO}_3[1\bar{1}0]$ and $\text{MgO}[1\bar{1}0]/\text{CoCr-alloy}[10.0]$.

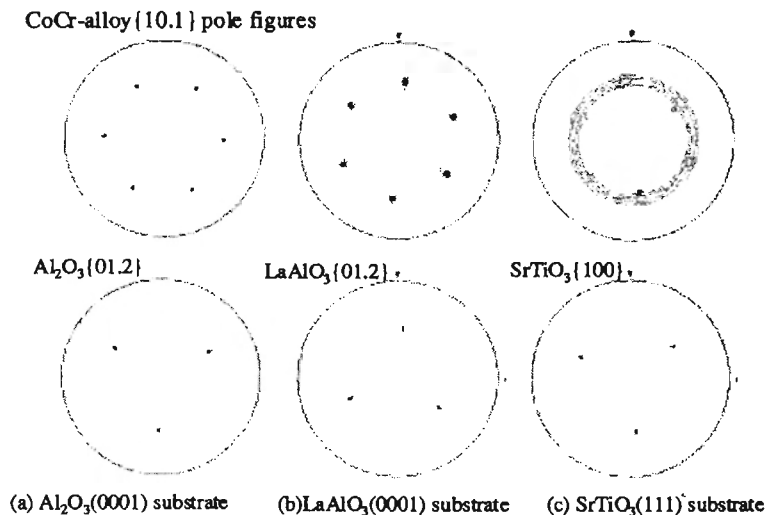


Figure 1 X-ray pole figure profiles of $\text{CoCrPt}/\text{CoCrRu}$ layer and oxide single-crystal substrates.

polycrystalline CoCrPt magnetic thin film was obtained on the mica(0001) substrate, was against our expectation, since the lattice mismatch was the minimum among the film/substrate combinations investigated here. The mismatch is calculated using the lattice parameter values of substrate and underlayer materials. Single-crystal thin films could not be obtained on the mica(0001) substrate even when the CoCrPt magnetic thin film was deposited directly and with either a TiCr₁₀ or a CoCr₄₀ non-magnetic underlayer. Although the reason why single-crystal thin films could not be obtained on the mica(0001) substrates is unclear, the possibility to grow CoCrPt single-crystal thin films on mica remains high if an optimum film growth condition can be found.

Figure 1 shows the X-ray pole figures of Co-alloy{10.1} and those observed for the Al₂O₃{01.2}, LaAlO₃{01.2}, and SrTiO₃{100} planes. Epitaxial growth of CoCr-alloy thin film was confirmed on these oxide single-crystal substrates. Here the {10.1} reflections from the CoCr₁₉Pt₁₀ film and CoCr₂₅Ru₂₅ underlayer are overlapped because of a small difference in the lattice parameter (CoCr₁₉Pt₁₀: $a=0.256$ nm, CoCr₂₅Ru₂₅: $a=0.258$ nm). The pole figures of Co-alloy{10.1} planes show clear six-fold symmetry. This result indicates that the Co-alloy films are single-crystalline and possess specific crystallographic orientation relationships with the respective single-crystal substrates. The crystallographic relationships between Co-alloy thin film and substrate are determined to be Co-alloy(0001)[21.0]//Al₂O₃(0001)[10.0] on Al₂O₃(0001) substrate, Co-alloy(0001)[10.0]//LaAlO₃(0001)[10.0] on LaAlO₃(0001) substrate, and Co-alloy(0001)[10.0]//SrTiO₃(111)[1-10] on SrTiO₃(111) substrate, respectively.

The sharpness of {10.1} pole reflections is related to the crystallographic quality of the Co-alloy thin film. The Co-alloy thin film grown on the Al₂O₃(0001) substrate shows the $\Delta\theta_{50}$ value of 0.6 degree and very sharp {10.1} pole reflections, while the thin film on the SrTiO₃(111) substrate shows the $\Delta\theta_{50}$ value of 5.1 degrees and {10.1} pole reflections with large dispersions. The CoCr₁₉Pt₁₀ magnetic single-crystal thin film grown on the SrTiO₃(111) substrate is supposed to include crystallographic defects such as sub-grain boundaries noted in the previous works [1,3].

Effect of underlayer material

It is shown that a good single-crystal CoCr₁₉Pt₁₀ magnetic thin film can be grown on the Al₂O₃(0001) substrate. Then the effect of underlayer on the crystallographic quality of CoCr₁₉Pt₁₀ thin film was investigated using the Al₂O₃(0001) substrate. Table II compares the $\Delta\theta_{50}$ value, $\Delta\alpha_{50}$ value, and the quality of CoCr₁₉Pt₁₀ magnetic thin film when deposited via non-magnetic *hcp* underlayers. The CoCr₁₉Pt₁₀ magnetic thin film was also deposited directly on the Al₂O₃(0001) substrate. The $\Delta\alpha_{50}$ value is the FWHM of α -scan around the CoCrPt(10.1) pole in the X-ray pole figure measurement carried out to estimate the dispersion. A small $\Delta\alpha_{50}$ value corresponds to small (10.1) pole dispersion. Figure 2 shows the X-ray pole figure profiles of non-magnetic underlayer (Ti, TiCr₁₀) and Co-alloy layers. It is clear that the CoCr₁₉Pt₁₀ magnetic thin film quality depends strongly on the underlayer material. The

Table II Effect of underlayer material on $\Delta\theta_{50}$ and $\Delta\alpha_{50}$ values of Co-alloy film grown on $\text{Al}_2\text{O}_3(0001)$ substrate

Underlayer	(no underlayer)	$\text{TiCr}_{10}(30\text{nm})$	$\text{CoCr}_{40}(50\text{nm})$	$\text{CoCr}_{25}\text{Ru}_{25}(50\text{nm})$	$\text{CoCr}_{25}\text{Ru}_{25}(10\text{nm})/\text{Ti}(50\text{nm})$
$\Delta\theta_{50}$ (degs)	3.5	3.0	2.2	0.6	0.9
$\Delta\alpha_{50}$ (degs)	4.0	5.1	3.3	1.8	2.3
Film quality	single-crystal	poly-crystal	poly-crystal	single-crystal	single-crystal

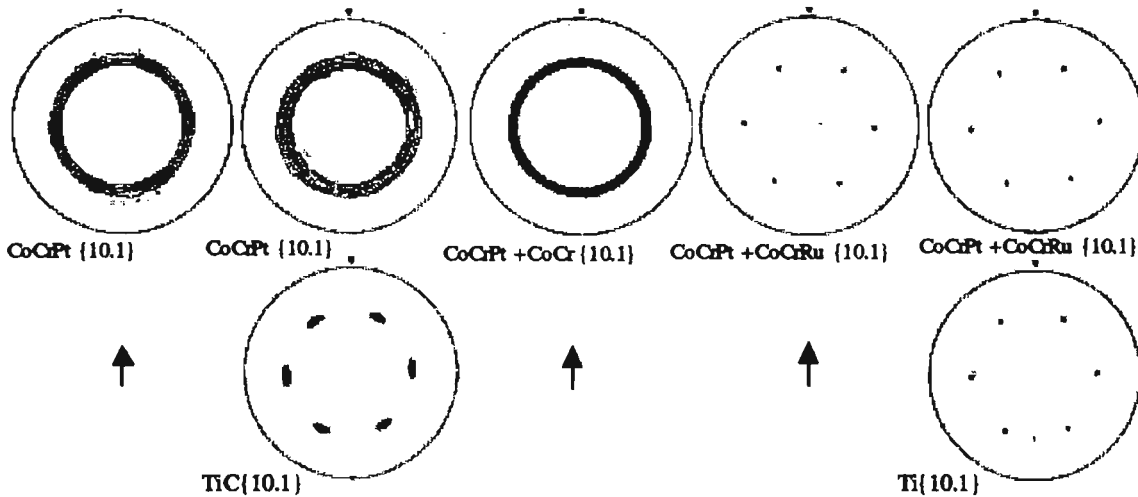


Figure 2 X - ray pole figure profiles of non-magnetic underlayer (Ti, TiCr) and CoCr-alloy layer. $\{10.1\}$ poles of CoCrPt, CoCr, and CoCrRu are overlapped due to similar lattice constants.

best single-crystal $\text{CoCr}_{19}\text{Pt}_{10}$ magnetic thin film is obtained when deposited via a non-magnetic $\text{CoCr}_{25}\text{Ru}_{25}$ underlayer. Although a single-crystalline $\text{CoCr}_{19}\text{Pt}_{10}$ magnetic thin film can be obtained on the $\text{Al}_2\text{O}_3(0001)$ substrate without any underlayer, the film quality is poor judging from the large values of $\Delta\theta_{50}(3.5 \text{ deg.})$ and $\Delta\alpha_{50}(4.0 \text{ deg.})$. The small mismatch in the lattice constant between the substrate and the deposited material does not explain the results shown in table II and figure 2. The $\text{CoCr}_{19}\text{Pt}_{10}/\text{CoCr}_{25}\text{Ru}_{25}$ layer is a good single-crystal, while the $\text{CoCr}_{19}\text{Pt}_{10}/\text{CoCr}_{40}$ layer is polycrystalline where the misfits against the $\text{Al}_2\text{O}_3(0001)$ substrate are similar for the respective underlayers ($\text{CoCr}_{25}\text{Ru}_{25}$: -6.12%, CoCr_{40} : -6.10%). It is also notable in figure 2 that the $\{10.1\}$ poles from Ti underlayer (mismatch: 7.3%) show narrower distribution than that from the TiCr_{10} underlayer with a little better mismatch of 7.1%. It seems necessary to take into account the other factor such as diffusion behavior of deposited materials on the substrate in the early stage of film growth to explain the results. An underlayer material that includes larger amount of Cr tends to show poor crystallographic quality. One possibility is that Cr element seems to suppress heteroepitaxial growth of deposited layer by suppressing the surface diffusion through combining selectively with oxygen atoms on the substrate surface. Addition of Ru to CoCr-alloy is considered to enhance surface diffusion when deposited on the $\text{Al}_2\text{O}_3(0001)$ substrate. Further studies are necessary to make clear this interpretation.

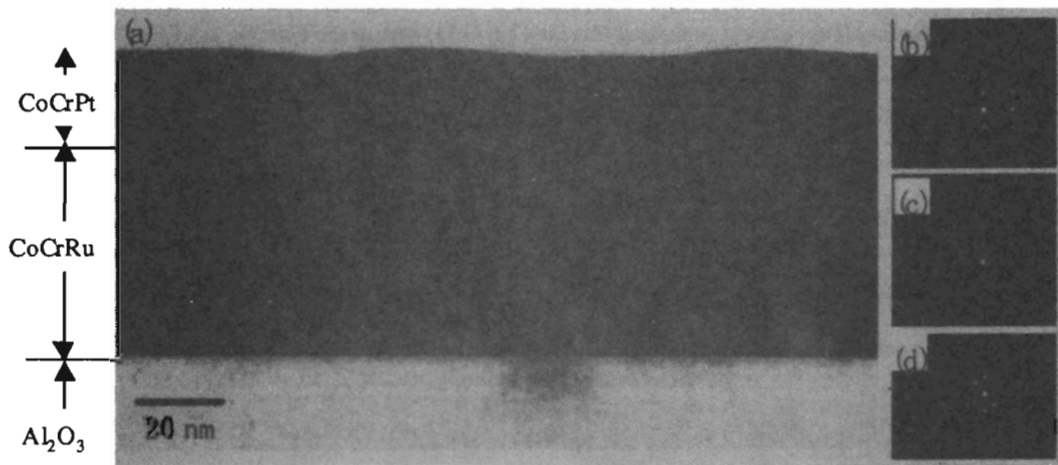


Figure 3 Cross-sectional structure and electron diffraction patterns of CoCrPt/CoCrRu/Al₂O₃ sample. (a) Cross-sectional structure. Electron diffraction patterns of (b), (c), and (d) were observed from CoCrPt, CoCrRu, and Al₂O₃ regions, respectively.

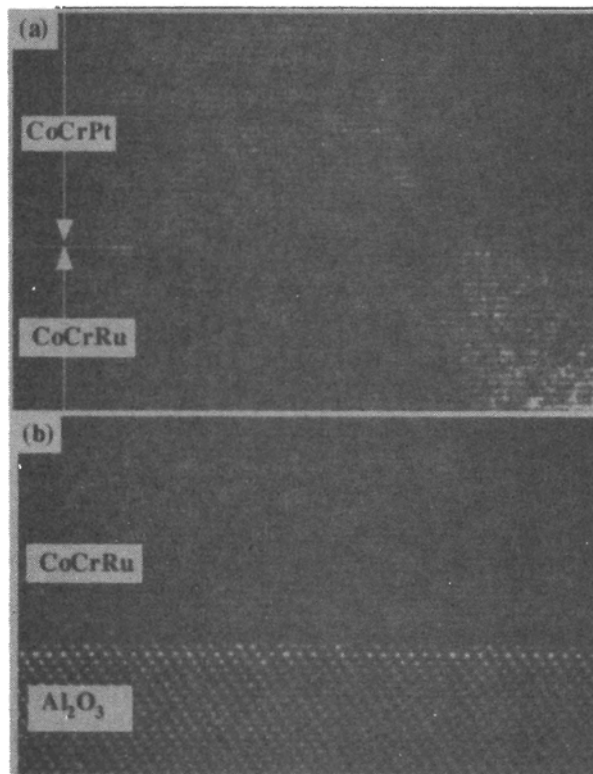


Figure 4 High-magnification TEM images of interfaces. (a) Interface between CoCrPt and CoCrRu underlayer. (b) Interface between CoCrRu underlayer and Al₂O₃ substrate.

Figure 3 shows the cross-sectional structure of a CoCr₁₉Pt₁₀(25 nm)/ CoCr₂₅Ru₂₅(50 nm)/ Al₂O₃(0001)

sample studied using a transmission electron microscope. There are no crystalline grain boundaries. In accordance with the X-ray pole figure results, a series of TEM diffraction patterns observed from the $\text{CoCr}_{19}\text{Pt}_{10}$ layer, the $\text{CoCr}_{25}\text{Ru}_{25}$ underlayer, and the $\text{Al}_2\text{O}_3(0001)$ substrate clearly indicates that the $\text{CoCr}_{19}\text{Pt}_{10}/\text{CoCr}_{25}\text{Ru}_{25}$ bi-layer is grown epitaxially on the $\text{Al}_2\text{O}_3(0001)$ substrate.

Figure 4 shows high-magnification TEM images observed around the interfaces of $\text{CoCr}_{19}\text{Pt}_{10}/\text{CoCr}_{25}\text{Ru}_{25}$ and $\text{CoCr}_{25}\text{Ru}_{25}/\text{Al}_2\text{O}_3(0001)$. Perfect hetero-epitaxy is realized between the $\text{CoCr}_{25}\text{Ru}_{25}$ nonmagnetic underlayer and the $\text{CoCr}_{19}\text{Pt}_{10}$ magnetic layer with no crystallographic defects around the interface.

Plan-view TEM structure of the $\text{CoCr}_{19}\text{Pt}_{10}$ magnetic layer is shown in figure 5. The sharp electron diffraction pattern and the high-resolution TEM picture clearly indicate that this film is a good quality single-crystal thin film and it has the easy magnetization axis (c-axis) perpendicular to the film plane.

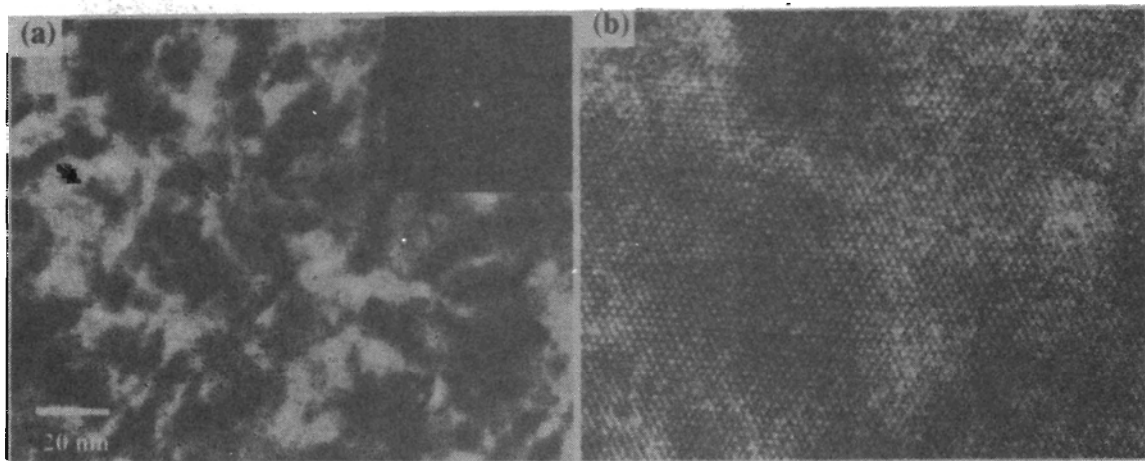


Figure 5 Plan-view TEM micrographs of single-crystal $\text{CoCr}_{19}\text{Pt}_{10}$ magnetic thin film grown on $\text{Al}_2\text{O}_3(0001)$ substrate. (a) Low magnification image and electron diffraction pattern. (b) High magnification lattice image.

Preparation of CoCr_xPt_y single-crystal thin films

CoCr_xPt_y single-crystal magnetic thin films were prepared employing the combination of $\text{CoCr}_{25}\text{Ru}_{25}$ underlayer (50 nm thickness) and $\text{Al}_2\text{O}_3(0001)$ single-crystal substrates. With this underlayer and substrate combination, it has been made clear that CoCrPt magnetic thin films with good crystallographic quality can be prepared. Here, we prepared CoCr_xPt_y single-crystal thin films by changing the Pt content to investigate the effect of Pt concentration on basic magnetic properties. The Cr content in the magnetic thin film is tried to keep constant at around 18 at%. Table III summarizes the average film composition, lattice parameter, lattice mismatch between magnetic layer and underlayer, local composition, and K_u value of CoCr_xPt_y single-crystal magnetic thin film. The thickness of magnetic layer was 50 nm. The average film composition was determined using Induction Coupled Plasma Spectroscopy (ICPS) and the local composition was investigated by using an EDAX-TEM. It is necessary to investigate the local distribution of alloy elements for these single-crystal magnetic thin

Table III Structural and magnetic properties of single-crystal CoCr-alloy thin films

Magnetic layer	Lattice parameter			Mismatch ¹⁾ (%)	Local composition (at%) ²⁾			Ku (280 K) x 10 ⁶ erg/cm ³
	a (nm)	c (nm)	c/a		Co	Cr	Pt	
CoCr ₂₀	0.253	0.406	1.605	-1.98	80.4 (0.66)	19.6 (0.66)	-	1.6
CoCr ₁₈ Pt ₇	0.255	0.410	1.606	-1.09	75.4 (1.04)	17.2 (1.12)	7.4 (0.61)	2.4
CoCr ₁₉ Pt ₁₀	0.256	0.413	1.610	-0.66	71.2 (1.45)	17.9 (1.47)	10.9 (0.59)	3.0
CoCr ₁₇ Pt ₁₇	0.258	0.416	1.613	-0.04	67.0 (0.96)	17.0 (0.80)	16.0 (0.67)	4.2
(CoCr ₂₅ Ru ₂₅)	0.258	0.411	1.593	-	-	-	-	-

Sample structure: CoCr-alloy thin film (50nm)/CoCr₂₅Ru₂₅(50nm)/Al₂O₃(0001).

1) Mismatch of *a* parameter between CoCr-alloy magnetic layer and CoCrRu underlayer.

2) Average local compositions are estimated from 24 spots analysis using EDAX-TEM.

Values in parenthesis are standard deviations (σ) of local fluctuation around the average compositions of Co, Cr, and Pt.

films, since a compositional inhomogeneity will change the local magnetic properties. Local fluctuations in alloy elements are expected because the Cr content in CoCr_xPt_y layer is exceeding the solubility limit in the phase diagram of Co-Cr alloy system. The excess Cr and possibly also Pt atoms may localize even in the single-crystal thin films under the influences of various origins including stress, strain, crystallographic defects, etc.

Figures 6 and 7 show the local compositional distributions measured for the single-crystal thin films of CoCr₄₀ and CoCr₁₇Pt₁₇, respectively. The electron beam diameter in the EDAX-TEM analysis was 2 nm. The local compositions were measured along the A – B and the C – D lines as indicated in the plan-view TEM pictures. Slight compositional variations of Co and Cr elements are recognizable around the average values of Co (80.4%) and Cr (19.6%) in the CoCr₂₀ single-crystal thin film. No apparent relation between the compositional fluctuation and the TEM contrast is observed. The compositional fluctuation with wavelength of 30 – 40 nm is noted in figure 6. Similar compositional fluctuations are recognized for the CoCr₁₇Pt₁₇ single-crystal thin film as shown in figure 7. The Pt distribution seems to be almost independent to those of other elements, while Cr shows an opposite distribution profile to that of Co. The Cr element fluctuation around the average composition (17.0 at%) of the CoCr₁₇Pt₁₇ single-crystal thin film is $\pm 1.6\%$ (2σ). The value is smaller than those observed for polycrystalline CoCr-alloy perpendicular recording media with similar Cr concentrations [6,7]. Local compositional analyses on CoCr₁₈Pt₇ and CoCr₁₉Pt₁₀ single-crystal thin films showed results similar to those of CoCr₂₀ and CoCr₁₇Pt₁₇ thin films depicted in figures 6 and 7.

The compositional fluctuation of Cr element is confirmed to be within ± 3 at% (2σ) for these single-crystal thin film samples. Pt element showed smaller fluctuations than that of Cr for all the samples as shown in the standard deviation values (α) listed in table III. A series of structural and compositional investigation has shown that the CoCr(Pt)-alloy thin films are single-crystals grown epitaxially on the Al₂O₃(0001) substrates and that these single-crystal thin films have compositional fluctuations of alloy elements to be within a few atomic percent around the average compositions.

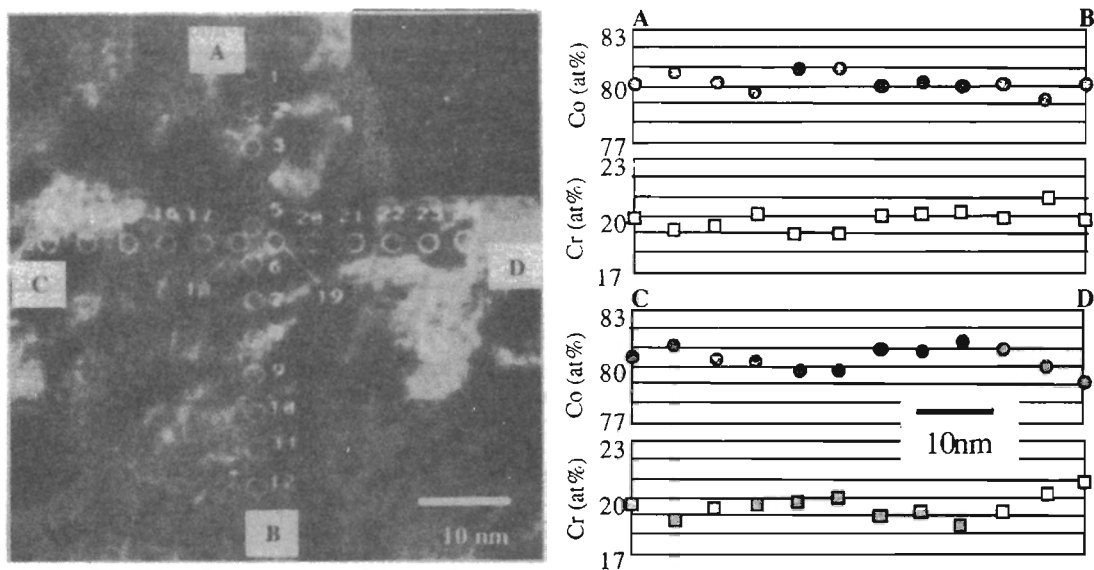


Figure 6 Local distributions of alloy elements measured for single-crystal CoCr_{20} magnetic thin film. Local compositions were measured for analysis points along A - B and C - D lines shown in plan-view TEM picture.

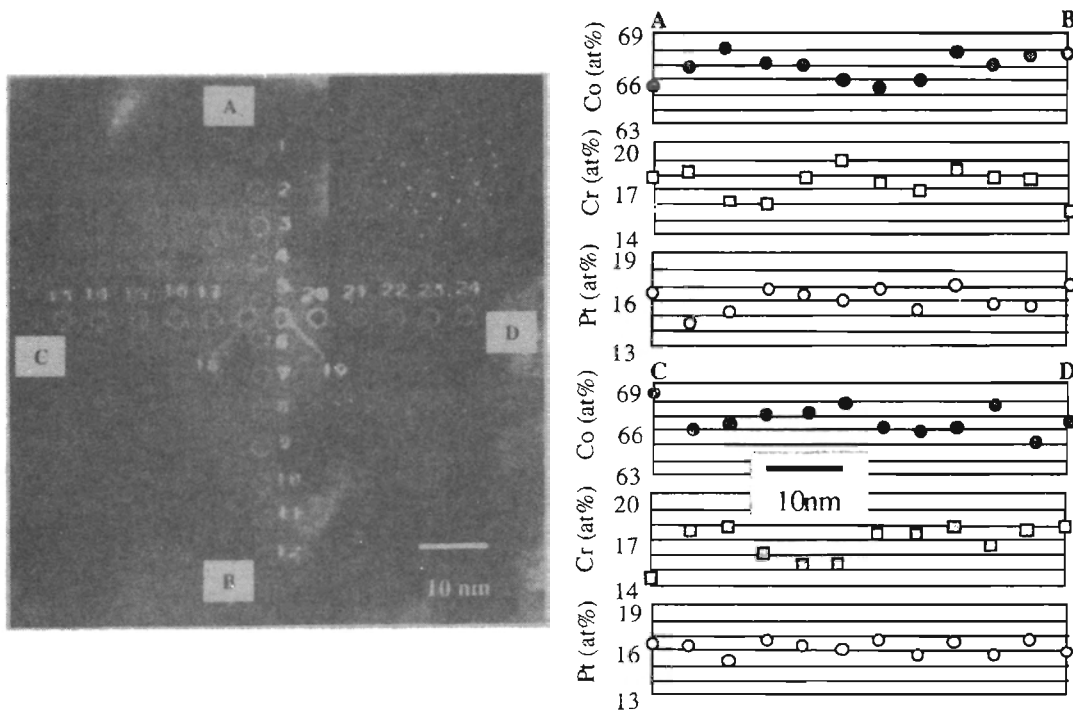


Figure 7 Local distributions of alloy elements measured for single-crystal $\text{CoCr}_{17}\text{Pt}_{17}$ magnetic thin film. Local compositions were measured for analysis points along A - B and C - D lines shown in plan-view TEM picture.

Magnetic properties of CoCrPt single-crystal thin films

Figure 8 shows the relationships between magnetic layer thickness and magnetic properties investigated using CoCr_xPt_y single-crystal thin films. K_u value increases with increasing the Pt concentration. The K_u values of CoCr_{20} , $\text{CoCr}_{18}\text{Pt}_7$, $\text{CoCr}_{19}\text{Pt}_{10}$, and $\text{CoCr}_{17}\text{Pt}_{17}$ single-crystal thin films (50 nm thickness) are respectively determined to be 1.6, 2.4, 3.0, and 4.2×10^6 erg/cc at 280 K. It is noted that H_k and K_u values tend to decrease with decreasing the magnetic layer thickness for all the compositions. This decreasing tendency is clear especially for the reduced magnetic layer thickness below around 25 nm. Possible reasons for the decrease in H_k and K_u are variations of local composition and crystallographic defect density close to

the interface and/or the surface. Slight increase of Cr content close to the interface and/or the surface will reduce the local H_k and K_u values. K_u value decreases with increasing number of stacking faults. Stacking faults are reported to exist preferentially close to the underlayer in CoCrPt perpendicular recording media [8]. Single-crystal magnetic thin films will be studied to clarify for this preference.

Single-crystal magnetic thin films are useful to accurately determine the intrinsic magnetic properties. They are also useful for finding methods to improve the magnetic properties as the magnetic layer thickness becomes thinner than 20 – 30 nm level. This seems to be an inevitable path for designing future perpendicular recording media.

CONCLUSIONS

Conditions to prepare good single-crystal CoCrPt magnetic thin films are investigated using oxide single crystal substrates. Some intrinsic magnetic properties are determined as functions of composition and thickness for the CoCrPt single-crystal magnetic thin films. The following results are obtained.

- (1) Single-crystal CoCrPt magnetic thin films with the c-axis perpendicular to the film plane can be grown on $\text{Al}_2\text{O}_3(0001)$, $\text{LaAlO}_3(0001)$, and $\text{SrTiO}_3(111)$ substrates. The best CoCrPt(0001) single

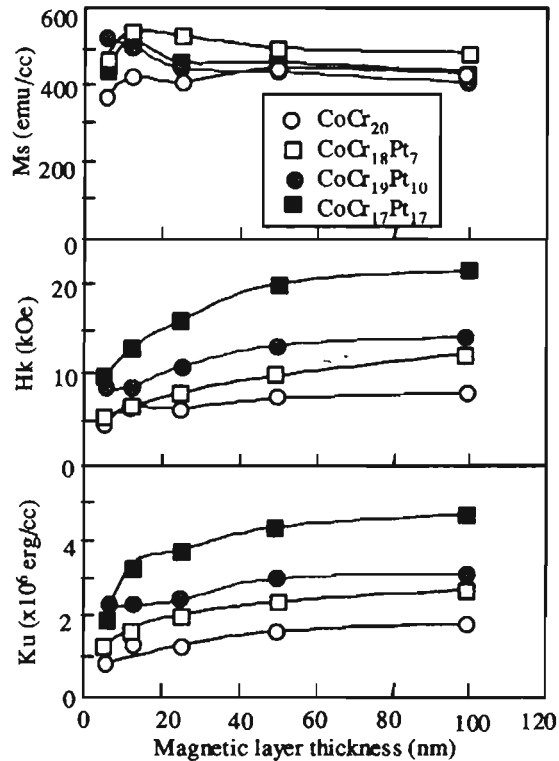


Figure 8 Magnetic properties of CoCr_xPt_y single-crystal thin films investigated as a function of layer thickness.

- crystal thin film with good crystallographic quality is obtainable on an $\text{Al}_2\text{O}_3(0001)$ substrate employing a suitable non-magnetic underlayer with an *hcp* structure.
- (2) The crystallographic quality of CoCrPt magnetic thin film strongly depends on the underlayer material. A high quality CoCrPt magnetic thin film is prepared when deposited on an $\text{Al}_2\text{O}_3(0001)$ substrate via a CoCrRu non-magnetic underlayer.
 - (3) Compositional fluctuations of alloy elements (Cr, Pt) are observed for single-crystal $\text{CoCr}_x\text{Pt}_y(0001)$ magnetic thin films ($x=17 - 20\text{at}\%$, $y=0 - 17\text{at}\%$). The fluctuations are confirmed to be less than ± 3 atomic percent (2σ) around the average compositions.
 - (4) Magnetic properties (H_k , K_u) are determined for the single-crystal CoCr_xPt_y magnetic thin films with different Pt concentrations. The K_u value tends to decrease when the magnetic layer thickness becomes smaller than about 25 nm where the influence from the interface and the surface of the magnetic layer becomes prominent.

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